In re Application of:

Arpan P. Mahorowala et al

Serial No.: 09/902,728

Filed: July 12, 2001

Atty Docket: YOR920000789US1

For: METHOD TO PREVENT PATTERN COLLAPSE IN FEATURES ETCHED IN

SULFER DIOXIDE-CONTAINING PLASMAS

## RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P. O. Box 1450 Alexandria 22313-1450

Sir:

In response to the Restriction Requirement dated April 7, 2003, Applicant elects Group I, drawn to a method classified in Class 430, subclass 322. Claims 1-17 and 20-21 are readable on the elected Group.

If the Examiner believes that an interview would facilitate the prosecution of this case, Applicants urge the Examiner to contact the undersigned at the telephone number listed below.

The undersigned hereby authorizes the Commissioner to charge any insufficient fees or credit any overpayment associated with this communication to Deposit Account No. 22-0185.

Respectfully submitted,

Date: May 15, 2003

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